

## OXIDE ETCH 200/300mm PROCESS OVERVIEW

### Who should attend?

This course is designed for those individuals in the semiconductor industry who require the knowledge and understanding of the Oxide Etch 200/300 Process Overview.

### Course Benefits

Increase knowledge of system components and their interrelationships.

### Course Objectives

- The basics of wafer manufacturing.
- Understanding basic etch chemistries.
- Explain the basics of RF plasma.
- Understand oxide etch dynamics.

### Course Modules

1. *Basic manufacturing*
2. *Basic process chemistries*
3. *Basic plasma physics*
4. *Process mechanisms*

### Registration Information

**Prerequisites:** *None*

**Course Length:** *1 Hour*

**Course Type:** *Web-based Training*

**Course Number:** *TRNWEB-59*

To enroll or for more information on our products and services, please call our registrar at one of the numbers below or go to [www.appliedtraining.com](http://www.appliedtraining.com).

- 1-800-468-8888, option 4 (United States)
- 1-512-272-0027 (International)

### Computer System Requirements:

Attending this course requires a Windows 98, NT, 2000 or XP computer using Internet Explorer 5.5 or higher. 128MB RAM or higher and high-speed Internet access is also highly recommended.